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QUERY CONTROL FORM		RTIS USE ONLY
Application No. 09/676512	Prepared by TE	Tracking Number 05933624
Examiner-GAU DEO - 1765		Week Date 4-12-04
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a. Serial No.	f. Foreign Priority	k. Print Claim(s)	p. PTO-1449	
b. Applicant(s)	g. Disclaimer	I. Print Fig.	q. PTOL-85b	
c. Continuing Data	h. Microfiche Appendix	m. Searched Column	r. Abstract	
d. PCT	, i. Title	n. PTO-270/328	s. Sheets/Figs	
e. Domestic Priority	j. Claims Allowed	o. PTO-892	t. Other	

SPECIFICATION	MESSAGE
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c. Holes through Data	
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h. Sequence Listing	
i. Appendix	
j. Amendments	
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- 27. (Original) The method of Claim 21 wherein the step of fabricating the fluid-handling component comprises the steps of:
 - (a) creating a mold pattern on a second substrate;
- (b) depositing a material for the fluid-handling component on the mold pattem;
 - (o) allowing the fluid-handling component material to harden; and
- (d) removing the hardened fluid-handling component material from the mold.
- 28. (Original) The method of Claim 27 wherein the step of creating a mold pattern on the second substrate comprises photolithography.
- 29. (Original) The method of Claim 21 wherein the step of fabricating the fluid-handling component comprises the steps of:
 - (a) creating an etching pattern on a second substrate; and
 - (b) etching the second substrate to form the contoured surface.
- The method of Claim 29 wherein the step of creating an etch pattern on the 30. second substrate comprises photolithography.
 - 31. (Original) The process of Claim 21 wherein the step of fabricating a fluid-handling component comprises:
 - (a) depositing a layer of metal on a second substrate;
 - (b) forming a pattern on the layer of metal;
 - (c) removing the portion of the metal layer covered by the pattern;
 - (d) forming at least one cavity in the second substrate, wherein the opening of the cavity corresponds to the portion of the metal layer that was removed in st p (c); and